



IAP/13
PATENT
P57015

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

HYUN-KI PARK, et al.

Serial No.: 10/791,830

Examiner: VAN, LUAN V

Filed: 4 March 2004

Art Unit: 1753

For: ELECTROMAGNETIC WAVE SHIELDING FILTER AND METHOD OF
MANUFACTURING THE SAME

INFORMATION DISCLOSURE STATEMENT

Mail Stop: Application Number

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In accordance with 37 C.F.R. §1.56, and §§1.97 and 1.98 as amended, Applicant cites, describes, and provides copies of the following art references:

FOREIGN PATENT REFERENCE(S):

- Korean Patent Publication No. 2000-0016858 to Lee, entitled *ANTI-REFLECTION AND ANTI-STATIC FILM*, published on 25 March 2000; and

- Korean Patent Publication No. 1999-0060730 to Cho, entitled *FILTER FOR PLASMA DISPLAY PANEL AND METHOD OF MANUFACTURING THE SAME*, published on 26 July 1999.

Folio: P57015

Date: 11/9/05

I.D.: REB/ms

OTHER DOCUMENT

- *Office Action* from the Korean Intellectual Property Office issued in Applicant's corresponding Korean Patent Application No. 10-2003-0026391 dated 18 August 2005.

DISCUSSION

As written in Office action issued by the Korean Intellectual Property Office on 18 August 2005 in applicant's corresponding Korean Patent Application corresponding to applicant's above-captioned U.S. Patent Application, **Lee'KR858** discloses that PURPOSE: An anti- reflection and anti-static film is provided to prevent a reduction of a light reflexivity a reduction of static electricity, and an interception of harmful electromagnetic wave from the outside of display panels like a Cathode-Ray Tube (CRT) and a Plasma Display Panel (PDP) by using a film made up a glass layer, and absorption layer, an adhesion layer, and a protection layer. CONSTITUTION: The anti-reflection and anti-static film comprises: a glass layer(51) for transmitting images in a display panel; an absorption layer(53) for preventing a static electricity of the light and a harmful electromagnetic wave transmitted from the glass layer and enriching a contrast by absorbing the constant amount of light; a adhesion layer(52) for adhering the glass layer and absorption layer to improve a reflexivity of light; and a protection layer(54) for being adhered at the absorption layer to protect a display panel from an air and a physical contact.

Cho'KR730 discloses that provided are a filter for a plasma display panel (PDP) and a method of manufacturing the same. The filter for PDP comprises a conductive pad 21a and a protection layer 22 on front and rear surfaces of an electromagnetic wave shielding filter 20. The method of manufacturing the filter for PDP comprises forming a metal deposition layer 21 on front and rear surfaces of an electromagnetic wave shielding filter 20; coating a protection layer 22 on the metal deposition layer 21; forming a photoresist layer 23 by coating the protection layer 22 with a

photoresist; and forming a conductive pad 21a by etching a peripheral portion of the protection layer 22 by photolithography. Therefore, an electromagnetic wave shielding effect is enhanced, noise is completely removed, and scratch is efficiently prevented, thereby ensuring better product quality, value, and competitiveness.

The citation of the foregoing references is not intended to constitute an assertion that other or more relevant art does not exist. Accordingly, the Examiner is requested to make a wide-ranging and thorough search of the relevant art.

Pursuant to 37 CFR § 1.97(d), the undersigned attorney hereby certifies that each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign patent application not more than three(3) months prior to the filing of the statement.

No fee is incurred by this Statement.

Respectfully submitted,

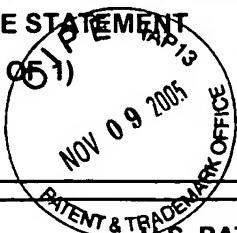


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INFORMATION DISCLOSURE STATEMENT
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APPLICANT HYUN-KI PARK, et al.

FILING DATE 4 March 2004

GROUP 1753

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

TRANSLATION

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
	KR 2000-0016858	03/00	Republic of Korea			Abstract	
	KR 1999-0060730	07/99	Republic of Korea			Abstract	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

Office Action from the Korean Intellectual Property Office issued in Applicant's corresponding Korean Patent Application No. 10-2003-0026391 dated 18 August 2005.

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP §609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.